

Method for producing a gas curtain of purge gas in a slit valve tunnel, and slit valve tunnel

Abstract

The invention relates to a method for producing a gas curtain of purge gas in a slit valve tunnel of a device for treating a semiconductor wafer and to a slit valve tunnel. The method comprises conducting the purge gas to two ends of a channel which is arranged in a head portion of the slit valve tunnel and is covered with a removable cover, and conducting the purge gas through a slit in the bottom of the channel as a gas curtain to a foot portion of the slit valve tunnel, while a semiconductor wafer is conveyed through a through-opening between the head portion and the foot portion of the slit valve tunnel.

Fig. 1